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Temporal and spatial distribution of negative ion density in a pulsed DC magnetron

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Reactive magnetron sputtering in argon-oxygen atmospheres is an important industrial technique for depositing engineering-quality dielectric thin films. Despite the success of this technique, there is still a lack of understanding of the role of negative ions in these discharges and their influence on the growth of the deposited oxide films.

Here, we present spatially and temporally-resolved measurements of the negative ion densities in a pulsed-DC magnetron discharge (100 kHz, 50% duty) obtained using an eclipse laser photo-detachment technique combined with a Langmuir probe. The probe was moved along the discharge centre line from 35 mm to 125 mm from the target and time-resolved measurements of electron and negative ion densities were obtained at each position. Around the position of the magnetic null ($B_z = 0$), the electron density reached a maximum ($1.9 \times 10^{16} \text{ m}^{-3}$ in the on-phase and $2.1 \times 10^{16} \text{ m}^{-3}$ in the off-phase); however the negative ion density was not a maximum at this position, still rising as the probe-target distance was increased. It was found that the electron density slightly increased during the on-phase, and then decreased during the off-phase, but the negative ion density showed the opposite trend, reaching a maximum of $9.8 \times 10^{15} \text{ m}^{-3}$ at $t = 5 \text{ ms}$ (end of the on-time). The data suggest that the negative ions seen in the off-time are created in the plasma bulk; while those observed in the on-time come largely from the cathode. The negative ion-to-electron density ratio, α was found to vary with operating conditions, with a maximum value of $\alpha \sim 0.7$ for 90 % argon and 10 % oxygen gas mixtures and an average power of 400W at 10 mTorr chamber pressure. This occurred just at the beginning of the on-time.

Keywords

negative ions diagnostic
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sputtering
laser photo-detachment